

<b>Session Title:</b>	<b>[WC3] Plasma Etch Simulation</b>
<b>Session Date:</b>	<b>November 16 (Wed.), 2022</b>
<b>Session Time:</b>	<b>15:10-16:20</b>
<b>Session Room:</b>	<b>Room C (Grand Ballroom 2, 2F)</b>
<b>Session Chair:</b>	<b>Prof. Ho-Jun Lee (Pusan Nat'l Univ., Korea)</b>

**[WC3-1] [Invited]** **15:10-15:40**

**Phase Resolved Plasma Dynamics of RF Capacitively Coupled Plasma Using Particle Trajectory Analysis**

**Cheol Woong Kim and Hae June Lee (Pusan Nat'l Univ., Korea)**

**[WC3-2]** **15:40-16:00**

**Computational Study of Necking Formation in Plasma Etching Processes Using Fluorocarbon Gases**

**Wonnyoung Jeong, Byoungyeop Choi, Youngseok Lee, Sijun Kim, Chulhee Cho, Inho Seong, Yebin You, Minsu Choi, and Shinjae You (Chungnam Nat'l Univ., Korea)**

**[WC3-3]** **16:00-16:20**

**Selective Etching Mechanism of Silicon Oxide Against Silicon by Hydrogen Fluoride: A Density Functional Theory Study**

**Romel Hidayat, Hye-Lee Kim, Khabib Khumaini, Tanzia Chowdhury (Sejong Univ. Korea), Tirta Rona Mayangsari (Universitas Pertamina, Indonesia), Byungchul Cho, Sangjoon Park (Wonik IPS, Korea), and Won-Jun Lee (Sejong Univ., Korea)**